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**IN THE CLAIMS:**

Please amend the claims as follows:

1. (Currently Amended) A thermally controlled apparatus for lining a processing chamber that defines a processing volume comprising:  
a base for substantially covering a bottom of the chamber;  
an inner wall connected to and extending upward from an inner side of the base;  
and,  
a substantially annular passage formed in the base, ~~the inner wall~~ or the base and the inner wall, the passage having an inlet and an outlet adapted to circulate a fluid through the passage, wherein the passage is fluidly isolated from the processing volume.
2. (Previously Presented) The apparatus of claim 1 further comprising an outer wall connected to an outer edge of the base for extending upward against a wall of the chamber.
3. (Original) The apparatus of claim 2 wherein the outer wall further comprises a pumping port.
4. (Original) The apparatus of claim 1 wherein the inner wall further comprises a magnet disposed in the inner wall.
5. (Original) The apparatus of claim 1 wherein the base is comprised of a material selected from the group of aluminum, ceramic and stainless steel.
6. (Original) The apparatus of claim 1 further comprising:

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a first and second boss projecting from the base, the first boss comprising a hole in fluid communication with the passage at the inlet, and the second boss comprising a hole in fluid communication with the passage at the outlet.

7. (Previously Presented) A thermally controlled apparatus for lining a processing chamber that defines a processing volume comprising:

a liner comprising a center member;

a flange circumscribing the center member;

a cylindrical wall projecting upward from the center member inside of the flange;

and

a substantially annular passage formed in the center member and having an inlet and an outlet adapted to circulate a fluid therethrough, wherein the passage is fluidly isolated from the processing volume.

8. (Original) The apparatus of claim 7 further comprising:

a lid disposed opposite the cylindrical wall, the lid and the wall defining a plenum at least partially therebetween.

9. (Original) The apparatus of claim 8 wherein the center member further comprises:

a plurality of nozzles disposed in the center member providing fluid access to the plenum.

10. (Original) The apparatus of claim 8 further comprising:

a gas feedthrough fluidly coupled to the plenum through a hole disposed in the lid.

11. (Previously Presented) A thermally controlled apparatus for lining a processing region defined at least partially by sidewalls and a bottom of a processing chamber, comprising:

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a liner adapted to be removably disposed in the processing region and having a base for substantially covering the bottom of the processing chamber; and

a passage formed at least partially in the base and adapted to fluidly isolate a heat transfer fluid flowing therethrough from the processing region, the passage being fluidly isolated from the processing region.

12. (Previously Presented) The apparatus of claim 11, wherein at least a portion of the passage is defined between the base and the bottom of the chamber.
13. (Previously Presented) The apparatus of claim 11, wherein the liner further comprises:  
a first boss and a second boss projecting from the base, the first boss comprising a hole in fluid communication with the passage at an inlet of the passage, and the second boss comprising a hole in fluid communication with the passage at an outlet of the passage.
14. (Original) The apparatus of claim 12, wherein the passage is a channel formed in a surface of the base and is adapted to be enclosed by the bottom of the chamber.
15. (Original) The apparatus of claim 11, wherein the liner comprises a cylindrical wall.
16. (Original) The apparatus of claim 15, wherein the passage is formed at least partially in the cylindrical wall.
17. (Original) The apparatus of claim 15, wherein the cylindrical wall comprises a lip extending into the process volume.
18. (Original) The apparatus of claim 15, wherein the cylindrical wall comprises a magnet disposed therein.

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19. (Original) The apparatus of claim 15, wherein the cylindrical wall comprises:  
a lip extending to the process volume; and  
a magnet disposed therein.
20. (Original) The apparatus of claim 15, wherein the cylindrical wall is configured to line the sidewalls of the chamber.
21. (Original) The apparatus of claim 15, wherein the cylindrical wall is configured to line a substrate support disposed in the process volume of the chamber.
22. (Previously Presented) The apparatus of claim 11, wherein the liner further comprises:  
an outer cylindrical wall connected to an outer edge of the base for extending into the processing region along the sidewalls;  
an inner cylindrical wall connected to an inner edge of the base for extending into the processing region along a substrate support; and  
a bottom coupled between the outer cylindrical wall and the inner cylindrical wall.
23. (Original) The apparatus of claim 11, wherein the liner is comprised of a material selected from the group of aluminum, ceramic and stainless steel.
24. (Original) The apparatus of claim 11, wherein the liner comprises:  
a textured interior surface adapted to be exposed to the interior volume.
25. (Previously Presented) A thermally controlled apparatus for lining a processing region defined at least partially by sidewalls and a bottom of a processing chamber, comprising:  
an annular base having a perimeter, for substantially covering the bottom of the processing chamber;  
a first cylindrical wall extending from the perimeter of the base; and  
a substantially annular passage formed at least partially in the base.

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26. (Original) The apparatus of claim 25, wherein the passage is adapted to isolate a heat transfer fluid flowing therethrough from the process volume.
27. (Original) The apparatus of claim 25, wherein the base further comprises:  
a first boss and a second boss projecting from the base, the first boss comprising a hole in fluid communication with the passage at an inlet of the passage, and the second boss comprising a hole in fluid communication with the passage at an outlet of the passage.
28. (Original) The apparatus of claim 25, wherein the passage is a channel formed in a surface of the base and is adapted to be enclosed by the bottom of the chamber.
29. (Original) The apparatus of claim 25, wherein the first cylindrical wall comprises a lip extending radially inwards in a spaced-apart relation to the base.
30. (Previously Presented) The apparatus of claim 25 further comprising a second cylindrical wall coupled to an inner portion of the base.
31. (Original) The apparatus of claim 25, wherein the base and first cylindrical wall are comprised of a material selected from the group of aluminum, ceramic and stainless steel.
32. (Original) The apparatus of claim 25, wherein the first cylindrical wall comprises a textured inner surface.
33. (Previously Presented) A thermally controlled apparatus for lining a processing region defined at least partially by sidewalls and a bottom of a processing chamber, comprising:  
an annular base for substantially covering the bottom of the chamber;

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a first cylindrical wall coupled to an outer portion of the base for extending into the processing region along the sidewalls of the chamber;

a second cylindrical wall coupled to an inner portion of the base for extending into the processing region along a substrate support positioned therein; and,

a substantially annular passage formed at least partially in the base, the passage being fluidly isolated from the processing region.

34. (Original) The apparatus of claim 33 further comprising at least one ridge extending between the first cylindrical wall and the second cylindrical wall in a spaced-apart relation to the base.

35. (Previously Presented) The apparatus of claim 33, wherein a passage is at least partially disposed in at least one of the first or second cylindrical walls.

36. (Previously Presented) A thermally controlled apparatus for lining a processing region at least partially defined by walls of a processing chamber, comprising:

a cylindrical liner section adapted to line at least a portion of the walls of the processing chamber;

a center section coupled to one end of the cylindrical section, the cylindrical section and the center section being exposed to the processing region and comprising a single piece structure, for substantially covering an upper surface of the chamber; and

a substantially annular passage at least partially formed in the center section, the passage being fluidly isolated from the processing region.

37. (Previously Presented) A thermally controlled apparatus for lining a processing region at least partially defined by walls of a processing chamber, comprising:

a center member for substantially covering an upper surface of the chamber, the center member having a first side adapted to be exposed to the processing region;

a cylindrical wall extending from the first side of the center member and adapted to line at least a portion of the walls of the processing chamber; and

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a substantially annular passage at least partially formed in the center member, the passage adapted to isolate a heat transfer fluid flowing therethrough from the processing volume.

38. (Original) The apparatus of claim 37 further comprising a lid disposed proximate the center member and defining a plenum at least partially therewith.

39. (Original) The apparatus of claim 38, wherein the center member further comprises a plurality of nozzles disposed in the center member providing fluid access between the plenum and a side of the center member opposite the lid.